FORM: PTO-1449 (REV: 7-80)		U.S. DEPARTMENT OF COMMERC PATENT AND TRADEMARK OFFICE				Atty Docket No: 2001-0827.01		Serial No:			
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.